

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 10-319595

(43)Date of publication of application : 04.12.1998

(51)Int.Cl.

G03F 7/039
C08L101/06
C09D 5/00
C09D201/06
H01L 21/027

(21)Application number : 09-130131

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(22)Date of filing : 20.05.1997

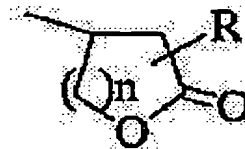
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(54) RESIST COMPOSITION AND RESIST PATTERN FORMING METHOD

(57)Abstract:

PROBLEM TO BE SOLVED: To make it possible to response to exposure light in the deep ultraviolet wavelength region typified by Krypton or Argon fluoride excimer laser beams and the like by incorporating an alkali-insoluble polymer made from a monomer having on the side chain a carboxylic group combined with a protective group having a specified polymer group, and solubilized in a basic solution, when this protective group is released from this side chain.

SOLUTION: The base polymer of this resist composition has the carboxylic group combined with the protective polymer group on the side chain in each monomer unit and it is insoluble in an aqueous basic solution, but when this protective polymer group is released from the side chain, the base polymer is made soluble in an aqueous basic solution. This protective polymer group is represented by the formula in which R is an H atom or a monovalent hydrocarbon group and it is linked to the site except the 3-position; and (n) is 1, 2, 3, or 4. When this resist film comprising this resist composition and a photo-acid-generator is exposed to the deep ultraviolet rays, an acid is produced in the exposed area and the protective polymer group of the carboxylic group is released to enhance sensitivity.



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[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision]